

MO2B-2

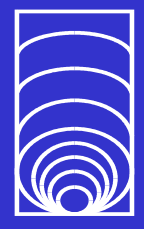
A Simplified CMOS FET Model using Surface Potential Equations For Inter-modulation Simulations of Passive-Mixer-Like Circuits

M. Baraani Dastjerdi and H. Krishnaswamy

CoSMIC Lab,

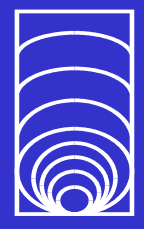
Columbia University, New York, United States





Outline

- Motivation and Prior Art
- Simplified Surface Potential Model
- Short-Channel Effects
- Simulation and Measurement Results
- Conclusion



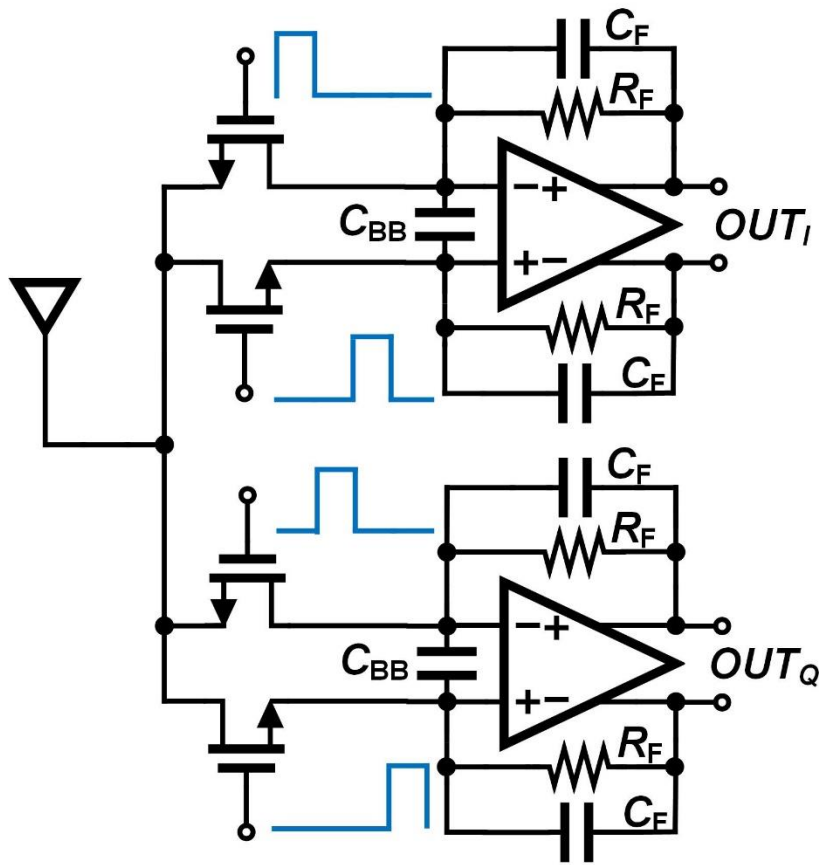
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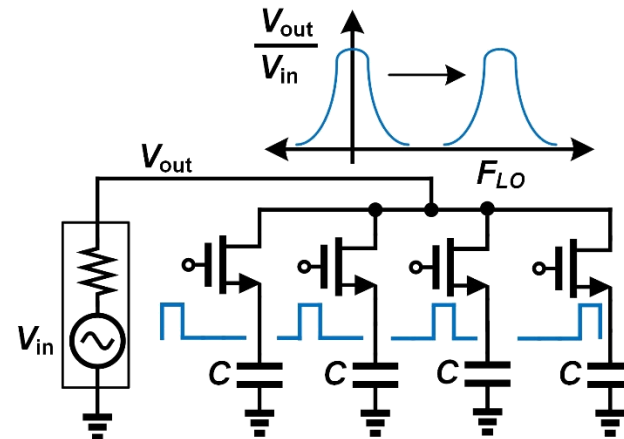
Circuits That Use FETs As Switches

Passive-Mixers and Mixer-First Receivers



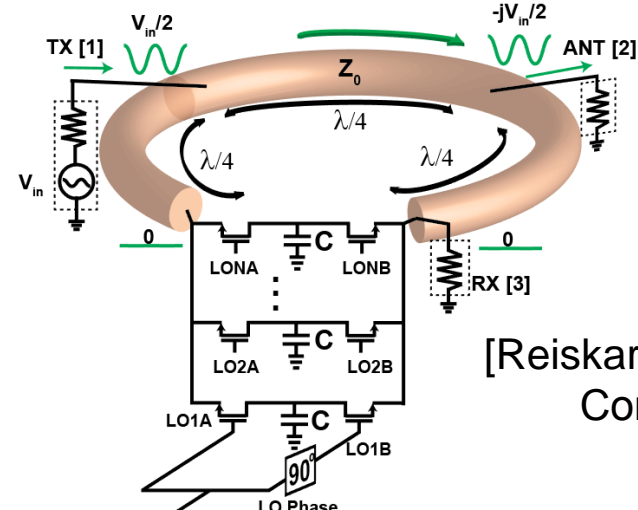
[Andrews JSSC'10]

N-Path Filters



[Ghaffari JSSC'13]

Integrated Circulators

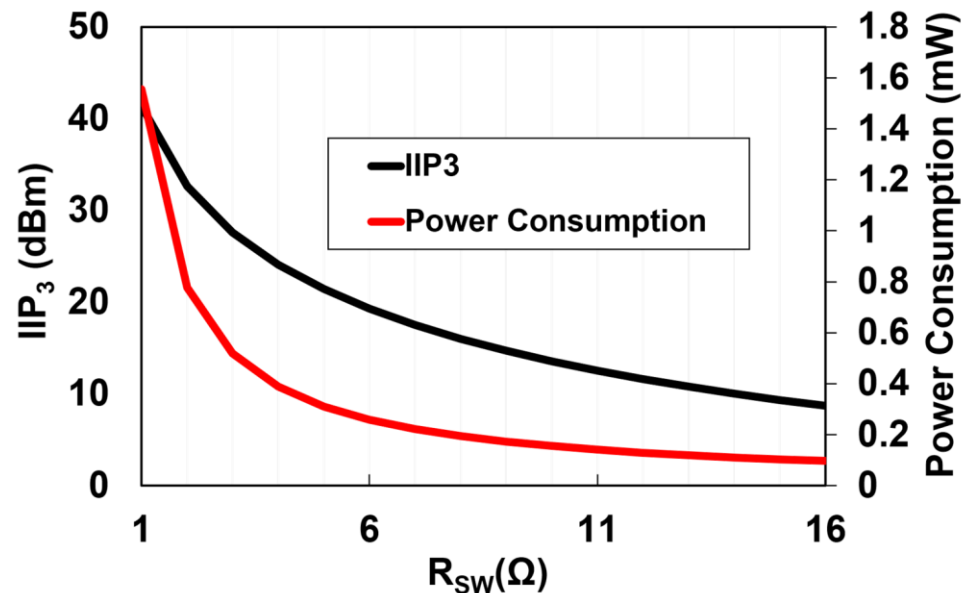
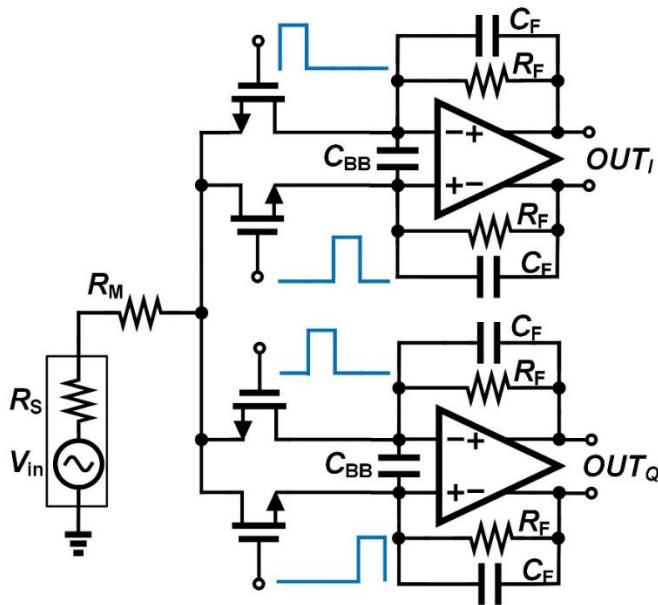


[Reiskarimian Nature Comm.'16]



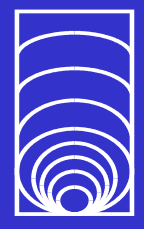
Mixer-First Receiver Design Challenges

- Increasing switch FETs size improves linearity at the cost of power consumption.
- Increasing series resistance R_M improves linearity at the cost of NF.

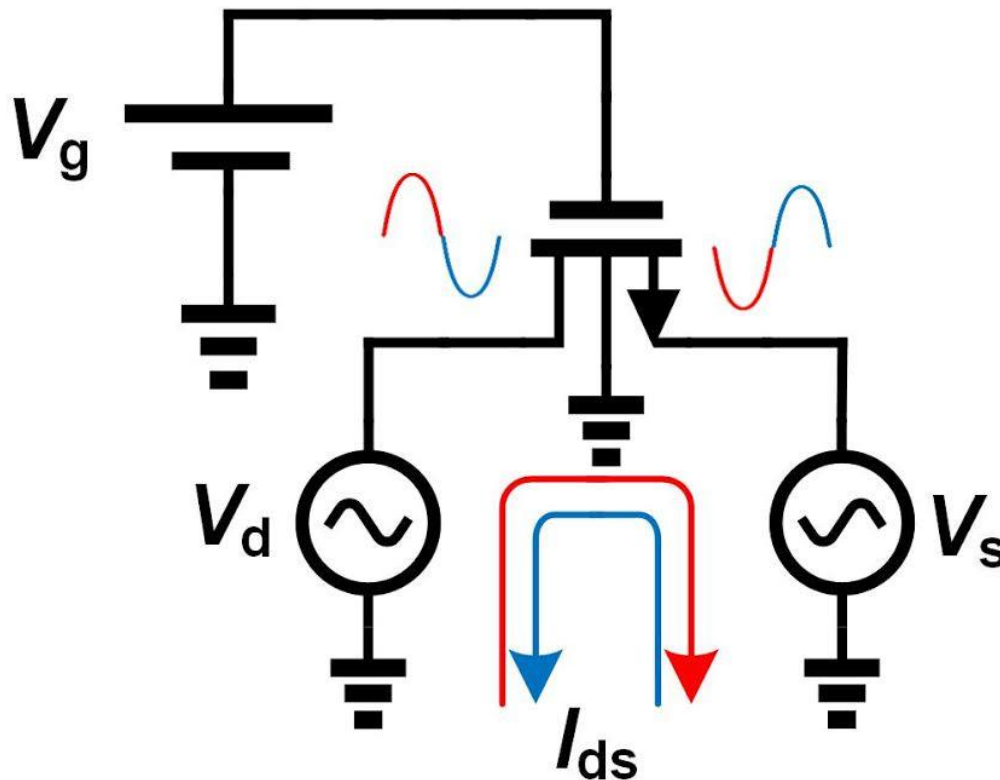


Out-of-band IIP₃ is calculated using [Yang TCASI'15]. Power consumption is calculated for an operating frequency of 1GHz.

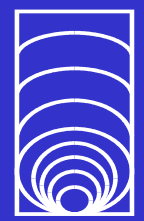
Linearity simulations are critical during the design phase for the optimization of passive mixer-like circuits.



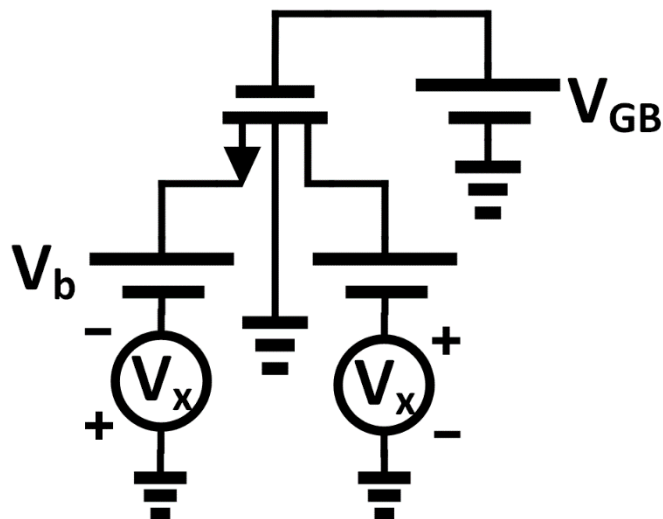
FET Operation As a Switch



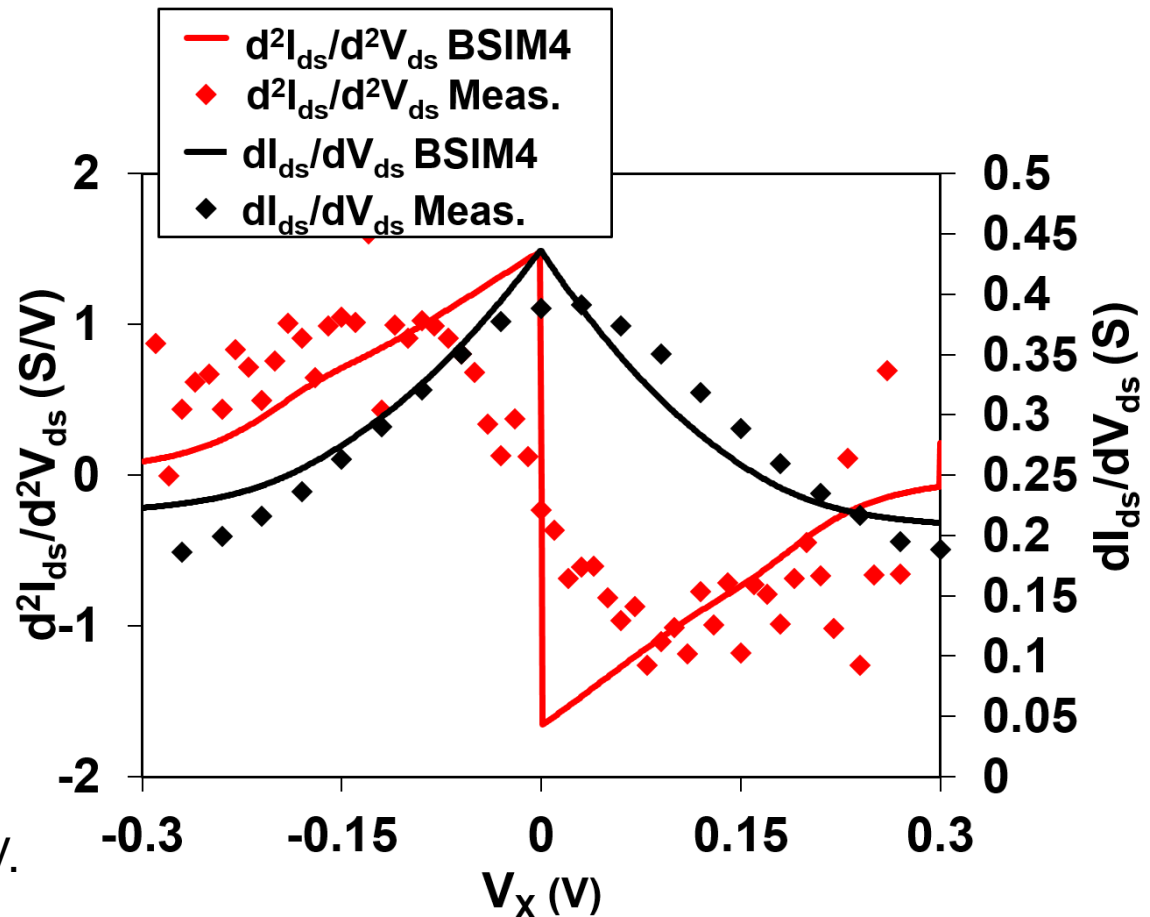
MOSFET switches are symmetric devices and typically experience source-drain reversal during AC operation.



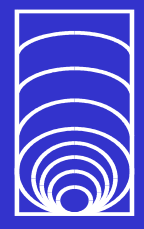
Gummel Symmetry Test In BSIM4



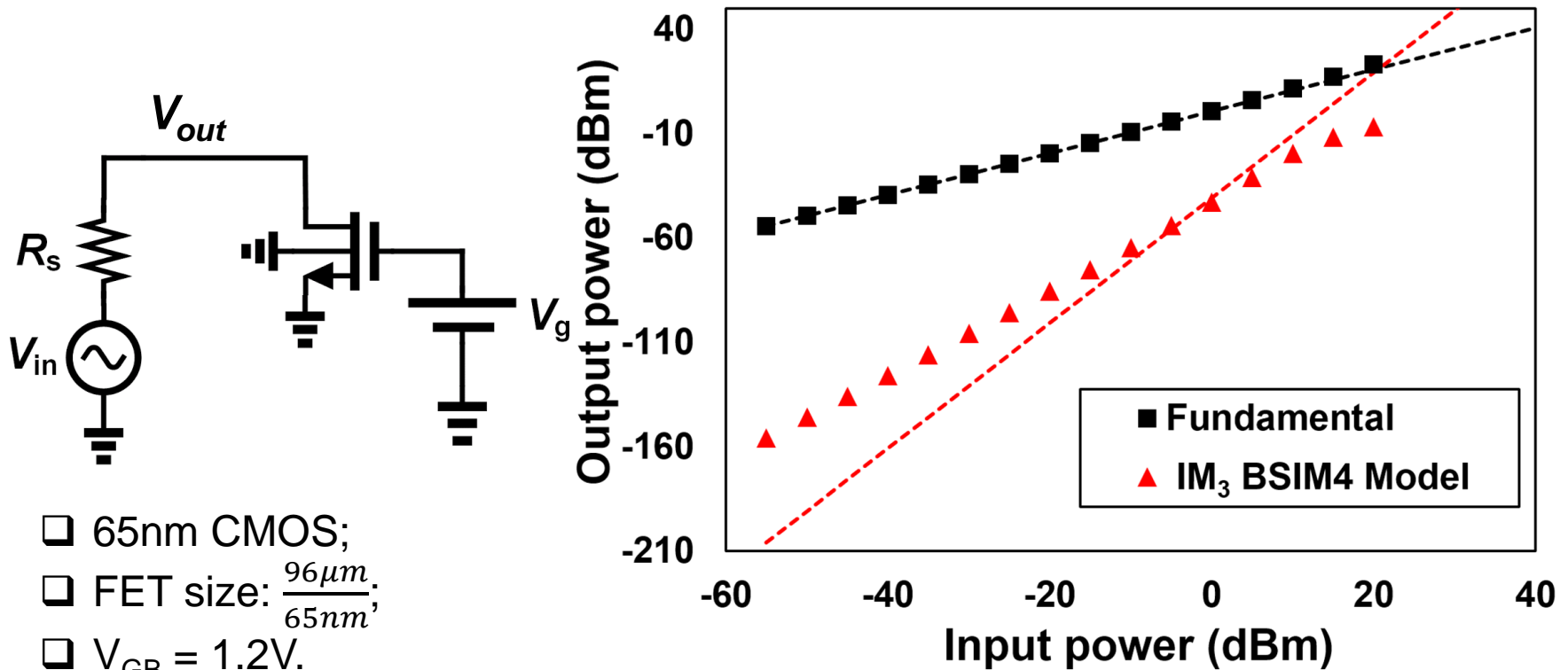
- 65nm CMOS;
- FET size: $\frac{96\mu m}{65nm}$;
- $V_{GB} = 1.2V$ and $V_b = 0.3V$.



In BSIM4 models, the 2nd derivative of I_{DS} shows discontinuity around $V_{DS}=0$.

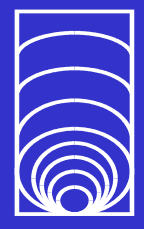


Two-Tone Test Using BSIM4 Model



- 65nm CMOS;
- FET size: $\frac{96\mu m}{65nm}$;
- $V_{GB} = 1.2V$.

The IM₃ predicted by BSIM4 models shows unphysical characteristics (slope of 2dB/dB).

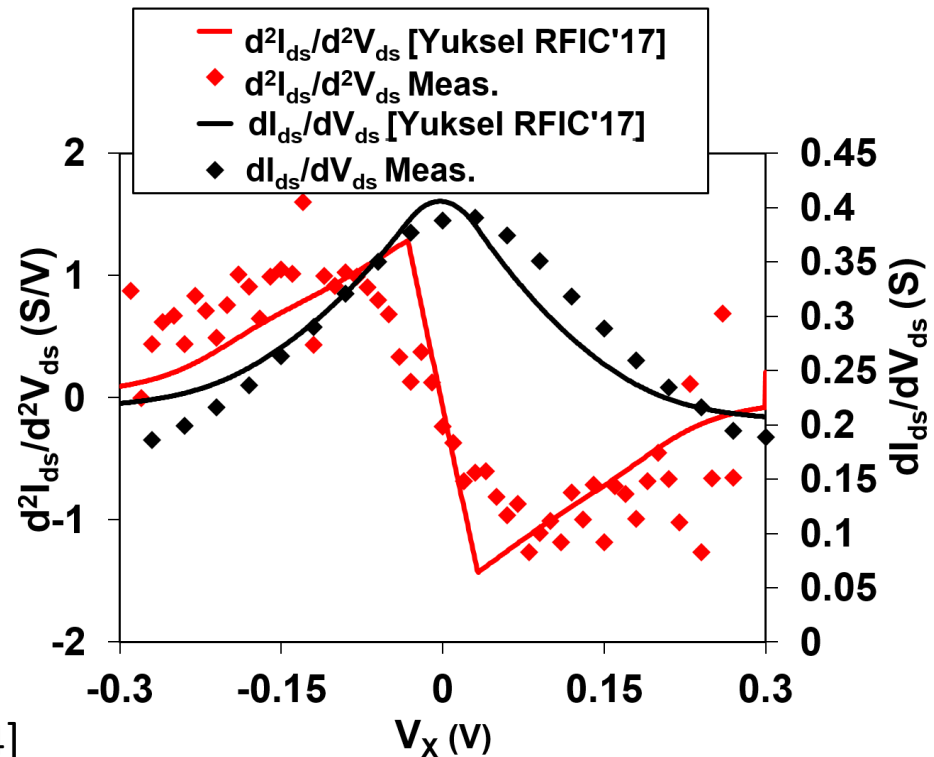
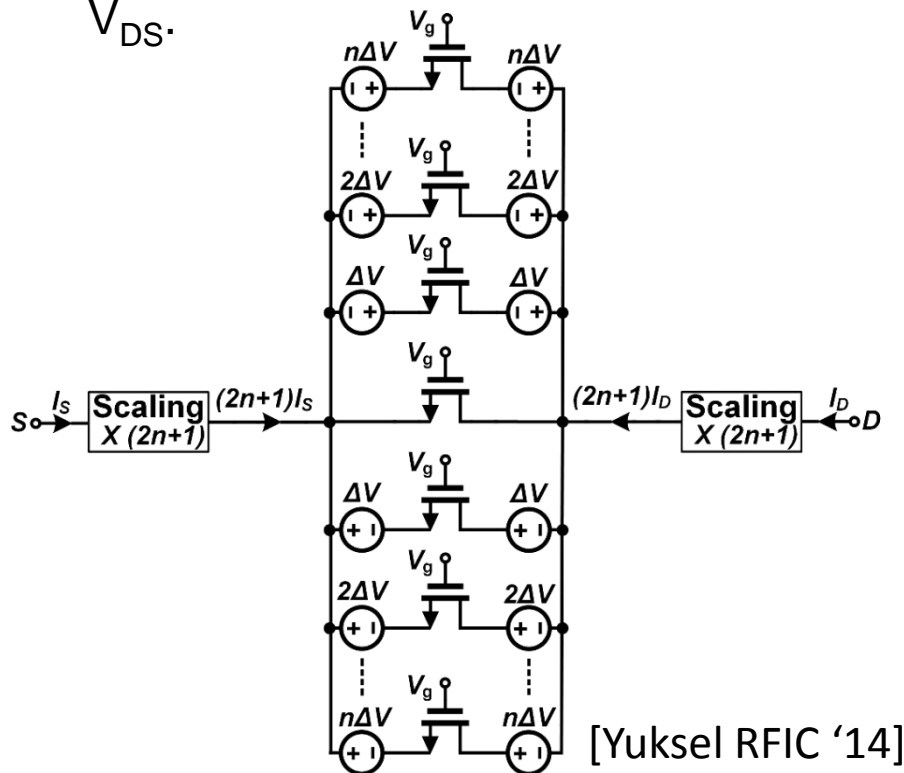


Transistor Models Comparison

Source-referenced models E.g. BSIM	Body-referenced models E.g. PSP
<ul style="list-style-type: none">✓ Physical driving forces are V_{GS} and V_{DS}.✓ V_T appears in the equations.✓ Velocity saturation is easy to handle.× Asymmetric around the source-drain reversal point.	<ul style="list-style-type: none">✓ Symmetry is appealing.✓ Effective mobility is well handled.✓ It is easy to make the drain current continuous at $V_{DS}=0$.× Not provided by most digitally-driven foundries.

Prior Work

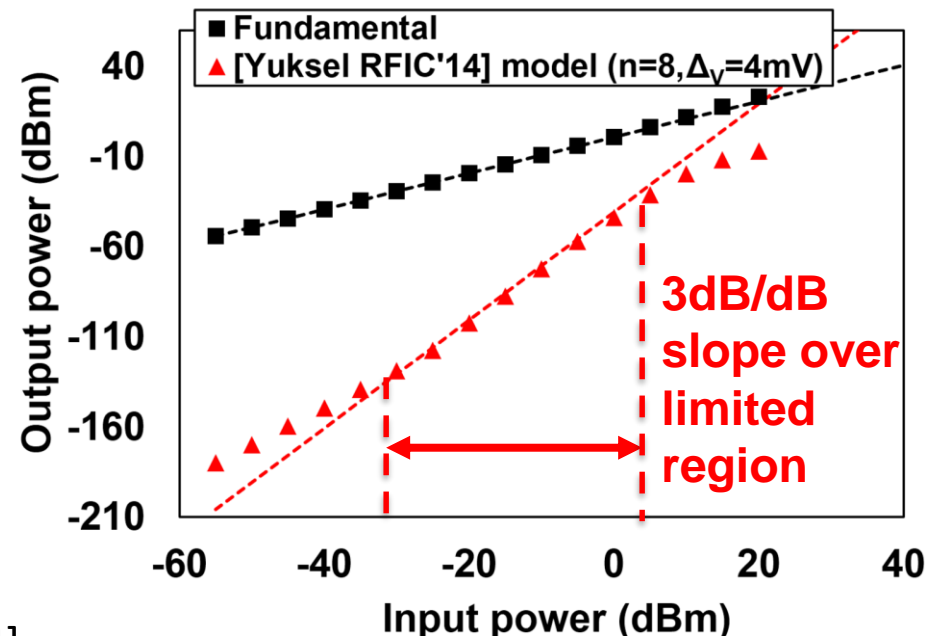
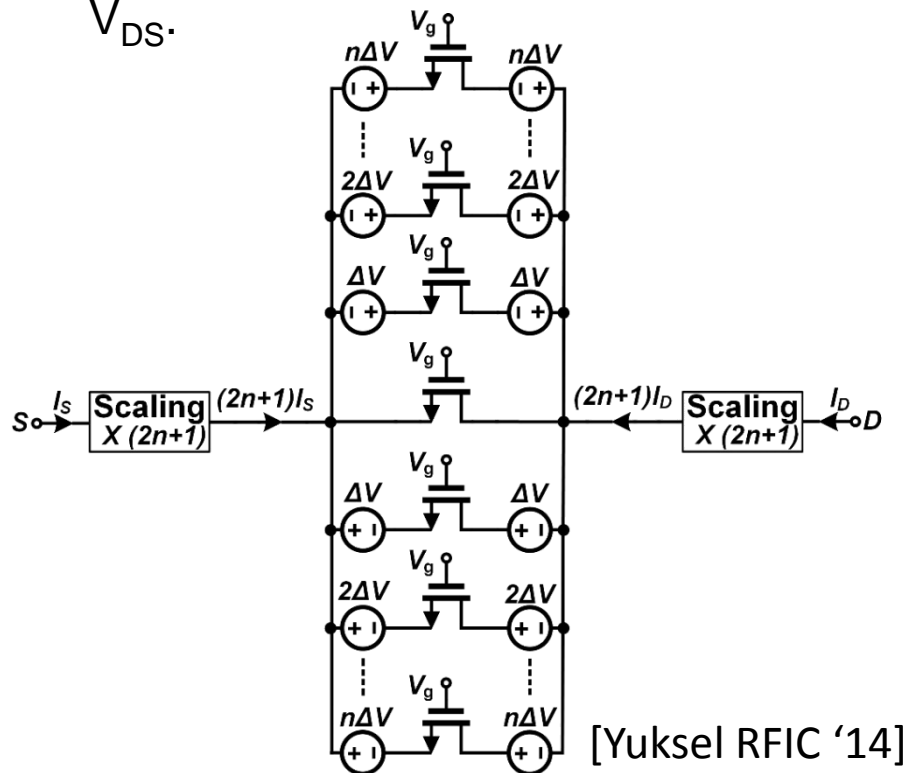
- Break the transistor into $2n+1$ transistors in parallel with small offset voltages in V_{DS} .



- ✗ High processing load (if $n=32$, 1 FET is replaced by 65 FET).
- ✗ Predicts 3dB/dB for IM_3 only for $\Delta V < V_{DS} < n\Delta V$.
- ✗ Need measurements to extract value of ΔV .

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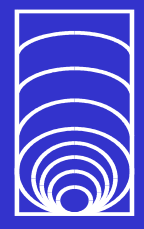


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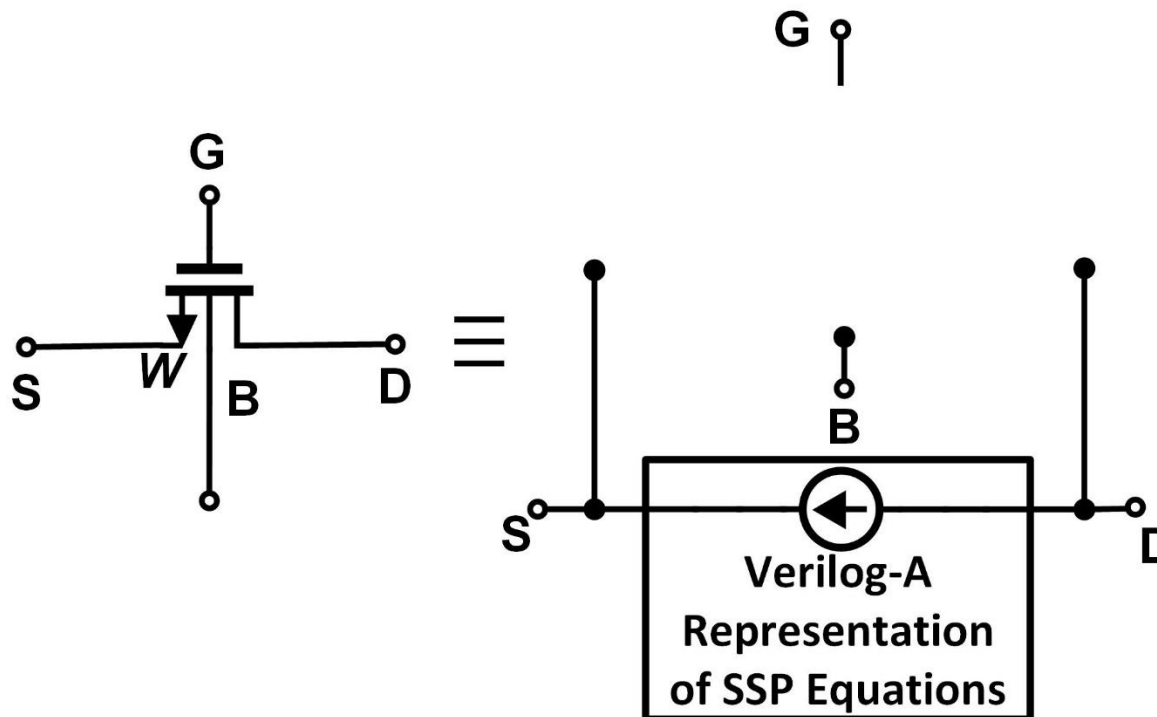
Outline

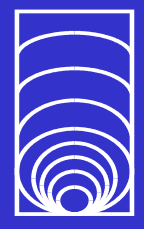
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- **Simplified Surface Potential Model**
- Short-Channel Effects
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Simplified Surface Potential Model

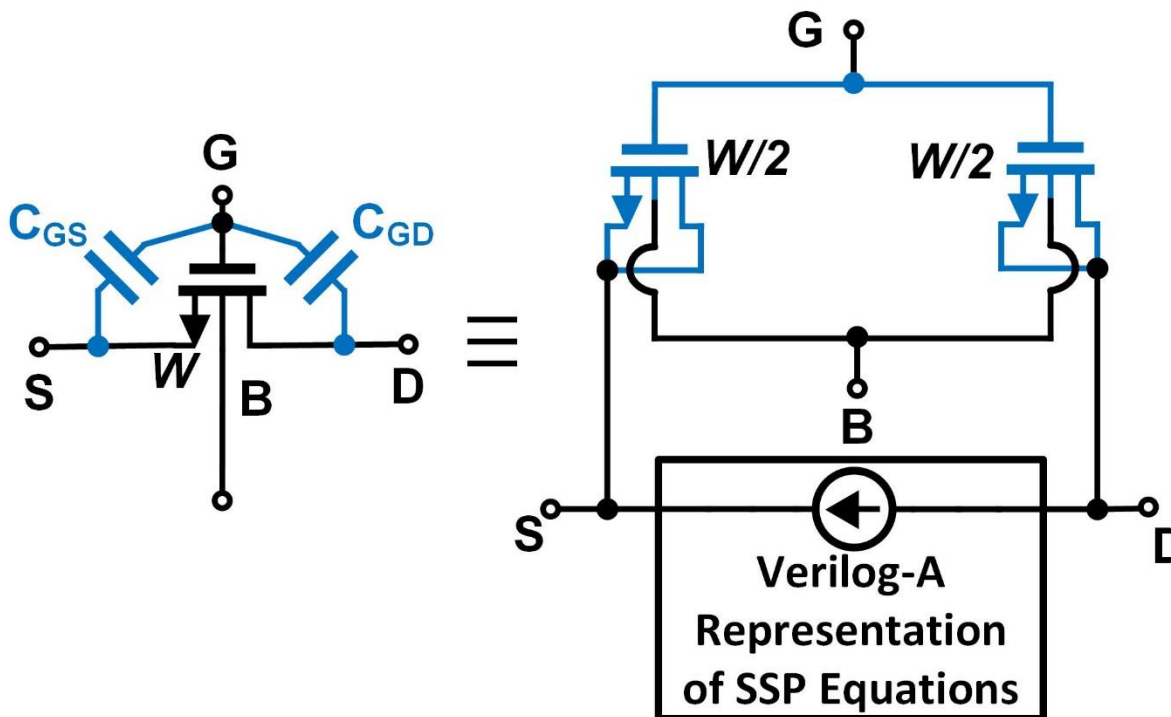
- Simple Verilog-A code is employed to define the I_{DS} based on FET terminal voltages using simplified surface potential (SSP) equations.





Simplified Surface Potential Model

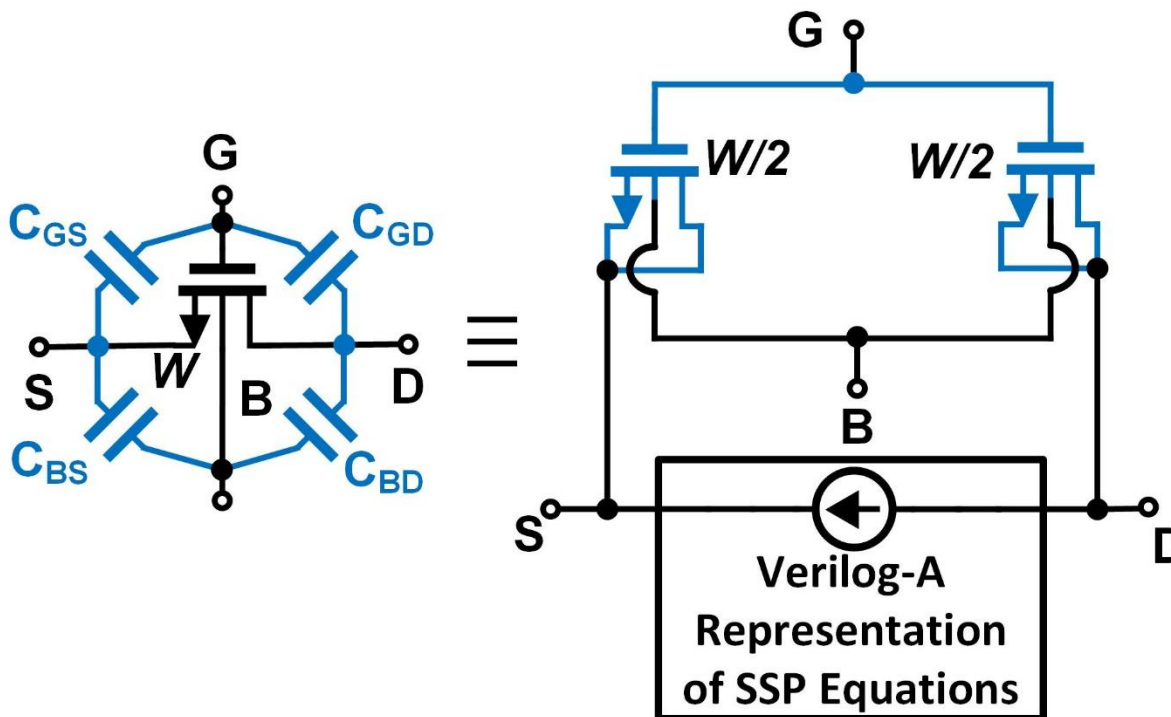
- Foundry provided model is used to take into account the 2nd order parasitics
 - Gate-source and gate-drain capacitance.





Simplified Surface Potential Model

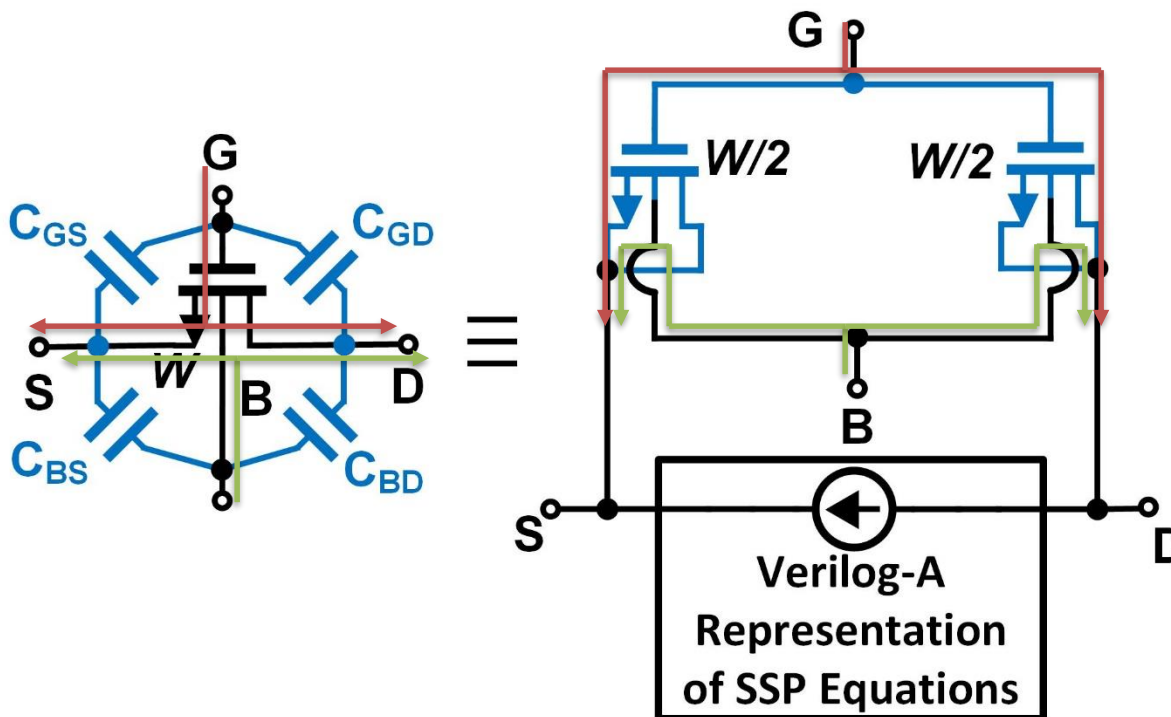
- Foundry provided model is used to take into account the 2nd order parasitics
 - Body-source and body-drain capacitance.





Simplified Surface Potential Model

- Foundry provided model is used to take into account the 2nd order parasitics
 - Gate and body leakage currents.

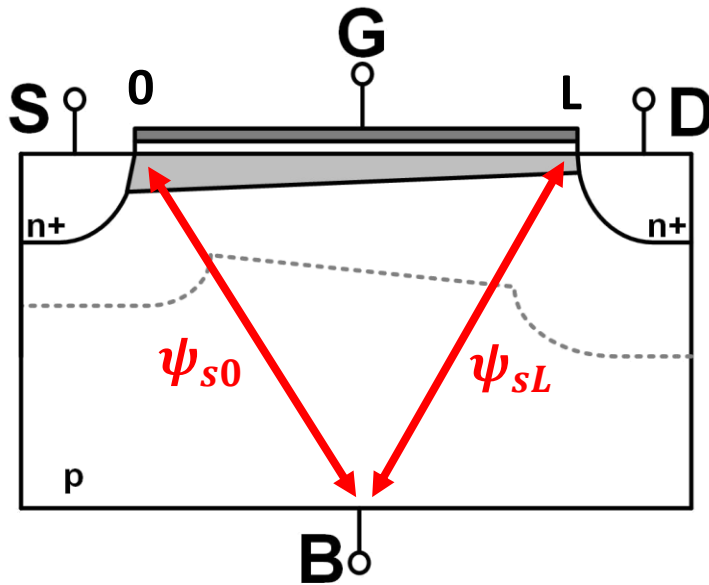


Surface Potential Equations

- Surface potential at source and drain ends can be described by*:

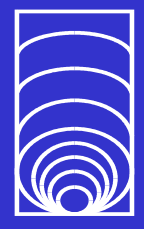
$$\psi_{s0} = V_{GB} - V_{FB} - \gamma \sqrt{\psi_{s0} + \phi_t e^{(\psi_{s0} - 2\phi_F - V_{SB})/\phi_t}}$$

$$\psi_{sL} = V_{GB} - V_{FB} - \gamma \sqrt{\psi_{sL} + \phi_t e^{(\psi_{sL} - 2\phi_F - V_{DB})/\phi_t}}$$



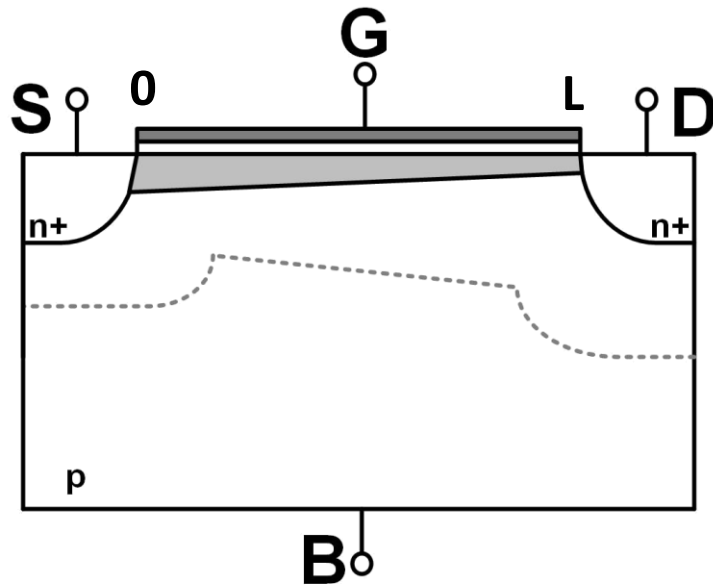
V_{FB} : Flat-band voltage
 γ : Body coefficient
 ϕ_F : Fermi voltage
 ϕ_t : Thermal voltage

* Y. Tsividis and C. McAndrew, Operation and Modeling of the MOS Transistor. Oxford Univ. Press, 2011.

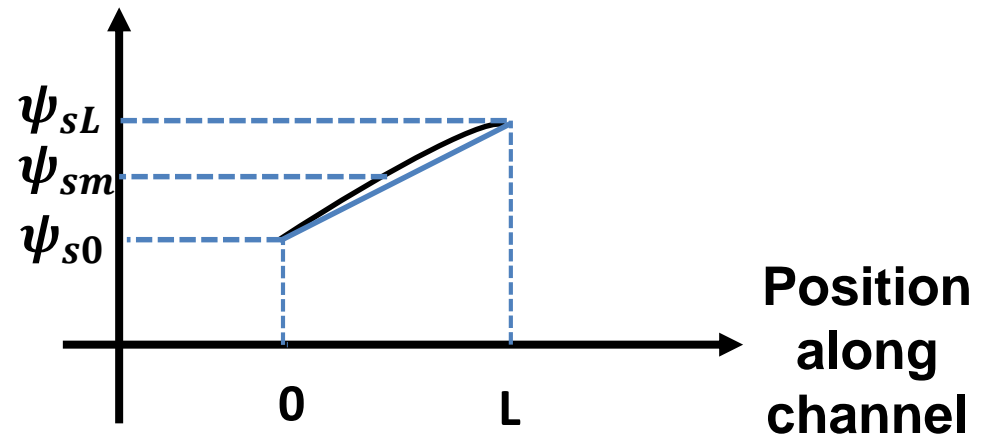


Surface Potential Along The Channel

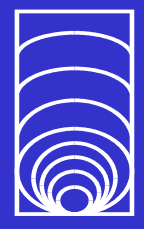
- Surface Potential along the channel can be approximated linearly.



Surface Potential



$$\psi_{sm} = \frac{\psi_{s0} + \psi_{sL}}{2}$$



Drain-Source Current Equation

- The drain-source current is a combination of drift and diffusion currents and can be approximated by*:

$$I_{DS,total} = I_{DS,drift} + I_{DS,diff}.$$

$$-I_{DS,drift} = \frac{W}{L} \mu C_{ox} (V_{GB} - V_{FB} - \psi_{sm} - \gamma \sqrt{\psi_{sm}}) (\psi_{sL} - \psi_{s0})$$

$$-I_{DS,diff} = \frac{W}{L} \mu C_{ox} \alpha_m \phi_t (\psi_{sL} - \psi_{s0})$$

$$\alpha_m = 1 + \frac{\gamma}{2\sqrt{\psi_{sm}}}$$

W : Width

L : Length

μ : Mobility of electron

V_{FB} : Flat-band voltage

γ : Body coefficient

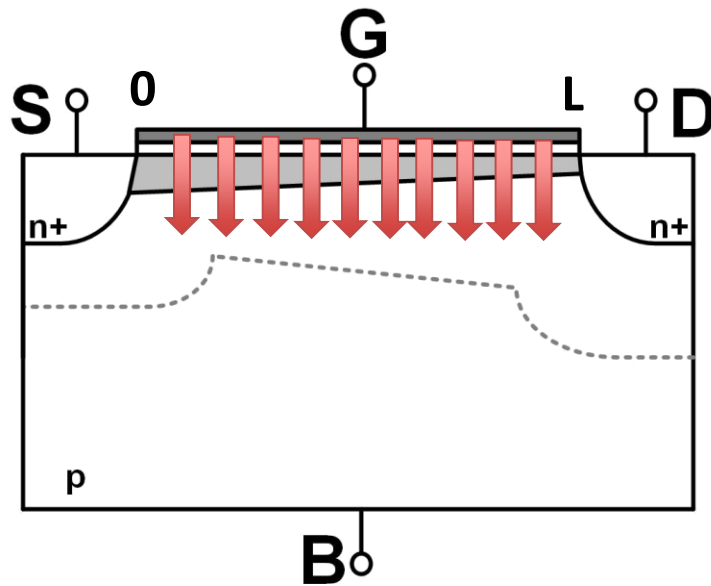
ϕ_F : Fermi voltage

Completely symmetric at $V_{DS}=0$.



Effective Mobility

- The mobility of electrons is reduced by the transverse field in the channel*.

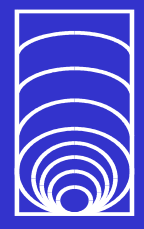


$$\mu_{eff} = \frac{\mu_0}{1 - \frac{a_0}{\epsilon_s} (\overline{Q'_B} + \eta_E \overline{Q'_I})}$$

$$\overline{Q'_B} = -C_{ox} \gamma \sqrt{\psi_{sm}}$$

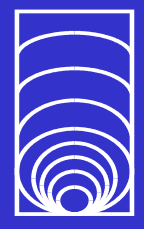
$$\overline{Q'_I} = -C_{ox} (V_{GB} - V_{FB} - \psi_{sm}) - \overline{Q'_B}$$

μ_0 , a_0 and η_E can be treated as curve fitting parameters.



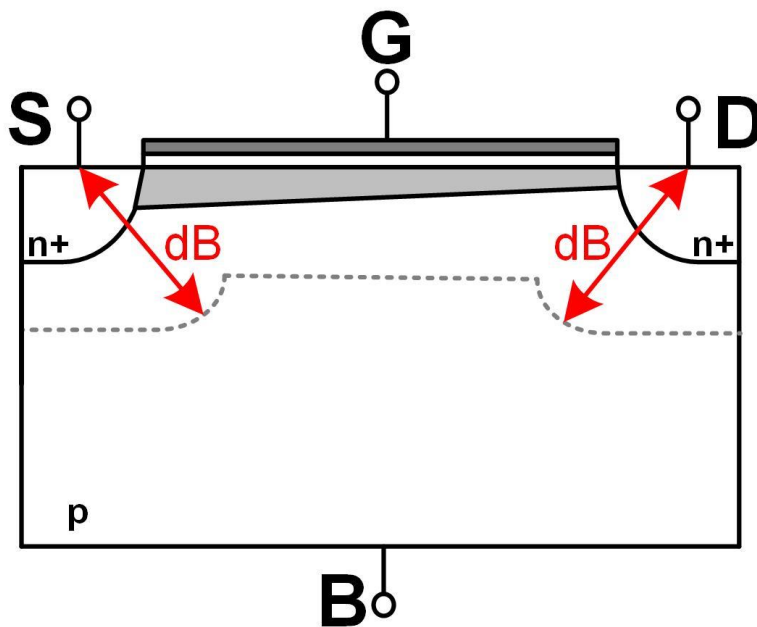
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Charge Sharing

- The extension of the drain and source depletion charge into the channel reduces the gate control over the channel charge.



$$\gamma_1 = \gamma \frac{\widehat{Q}_B}{Q_B}$$

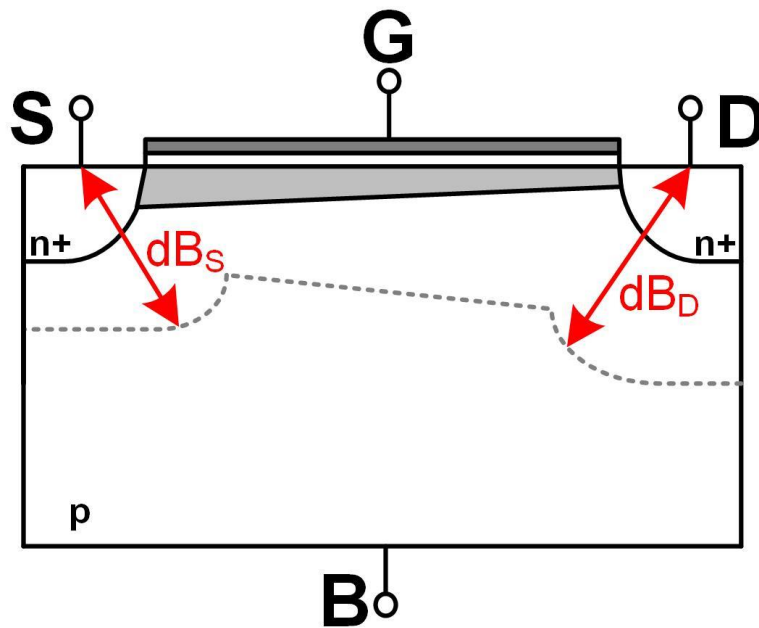
$$\frac{\widehat{Q}_B}{Q_B} = 1 - \frac{d_j}{L} \left(-1 + \sqrt{1 + 2 \frac{dB}{d_j}} \right)$$

Depletion region is not necessarily same around the source and drain.



Charge Sharing

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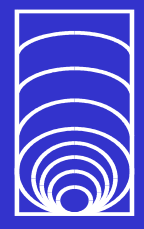
$$\frac{\widehat{Q}_B}{Q_B} = 1 - \frac{\Delta_S}{L} \left(1 - \frac{dB_S}{2dB}\right) - \frac{\Delta_D}{L} \left(1 - \frac{dB_D}{2dB}\right)$$

$$\Delta_{S/D} = d_j \left(-1 + \sqrt{1 + 2 \frac{dB_{S/D}}{d_j}} \right)$$

$$dB = \frac{dB_S + dB_D}{2}$$

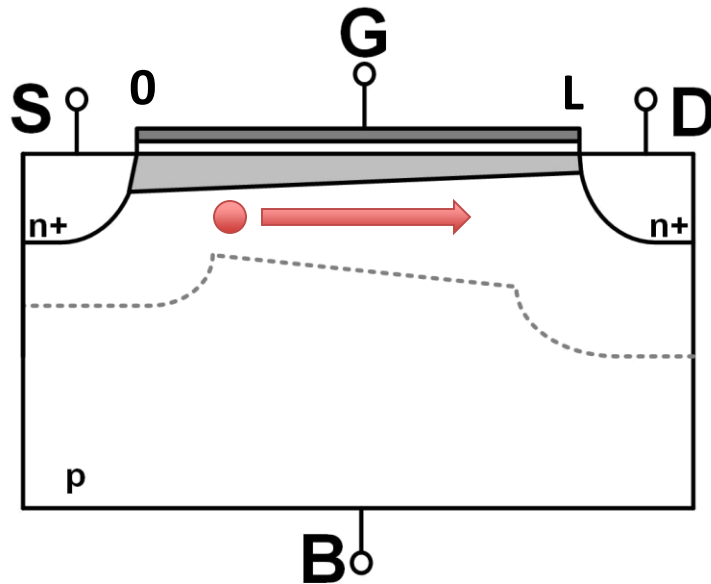
d_j : Junction depth

Completely symmetric at $V_{DS}=0$.

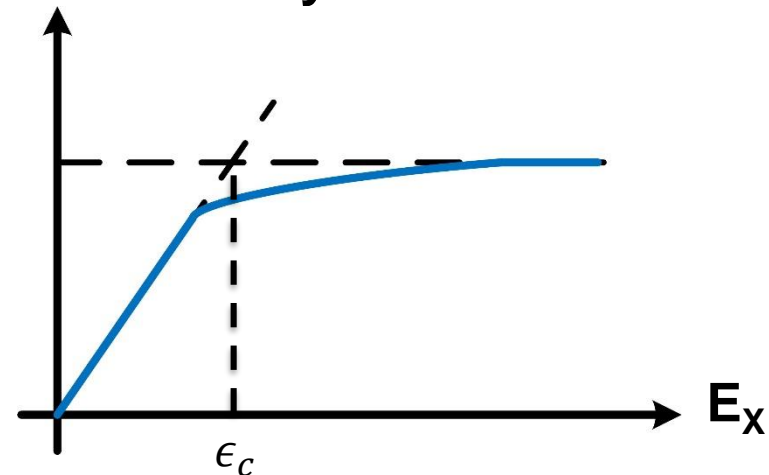


Velocity Saturation

- Velocity of carriers can saturate even with device operating in triode.

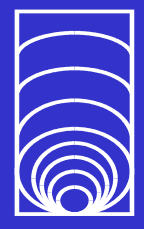


Carrier velocity



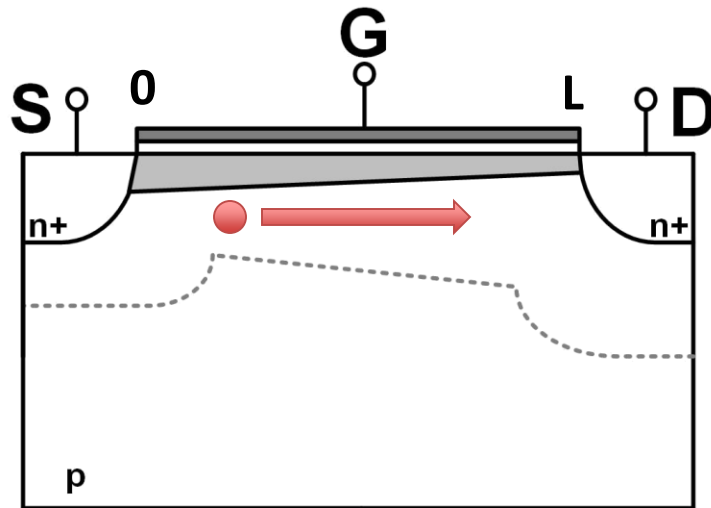
$$-I_{DS,w \text{ Velocity Saturation}} \neq \frac{-I_{DS,w/o \text{ Velocity Saturation}}}{1 + \frac{V_{DS}}{L\epsilon_c}}$$

Second order derivatives are discontinuous.

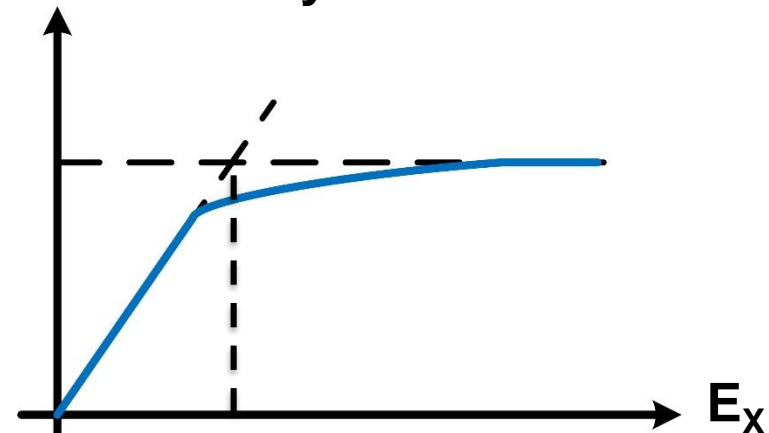


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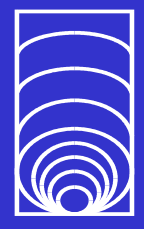


Carrier velocity



$$-I_{DS,w \text{ Velocity Saturation}} = \frac{\epsilon_c}{0.5(1 + \sqrt{1 + 2 \left(\frac{V_{DS}}{L\epsilon_c} \right)^2})}$$

Accurately models the current and its derivatives.



Channel Length Modulation

- Channel length modulation can be described as:

$$L_{eff} = L - l_p$$
$$l_p = l_a \times \ln \left(1 + \frac{V_{DSX} - V_{DS,eff}}{V_e} \right), l_a = \sqrt{3t_{ox}d_j}$$

t_{ox} : gate oxide thickness

d_j : source and drain junction depth

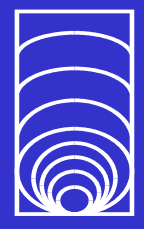
V_e : Early voltage

- Smoothing functions are employed to ensure about the continuity of the current around $V_{DS}=0^*$:

$$V_{DS,eff} = \frac{V_{DS}}{(1 + (\frac{V_{DS}}{V'_{DS}})^{10})^{0.1}}, V_{DSX} = \sqrt{V_{DS}^2 + 0.01} - 0.1$$

V'_{DS} : Smoothing function constant

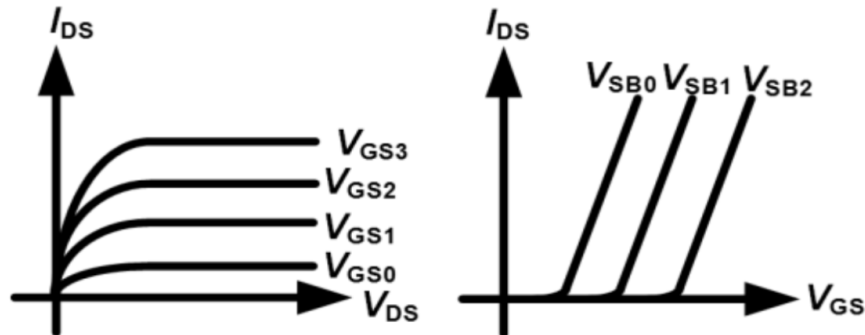
*X. Li et al., "PSP 102.3," NXP Semiconductors, Tech. Rep. 2008.



Model Parameter Extraction

Foundry provided model

Simulator



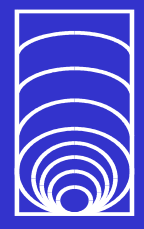
Curve-fitting using MATLAB

SSP model parameters

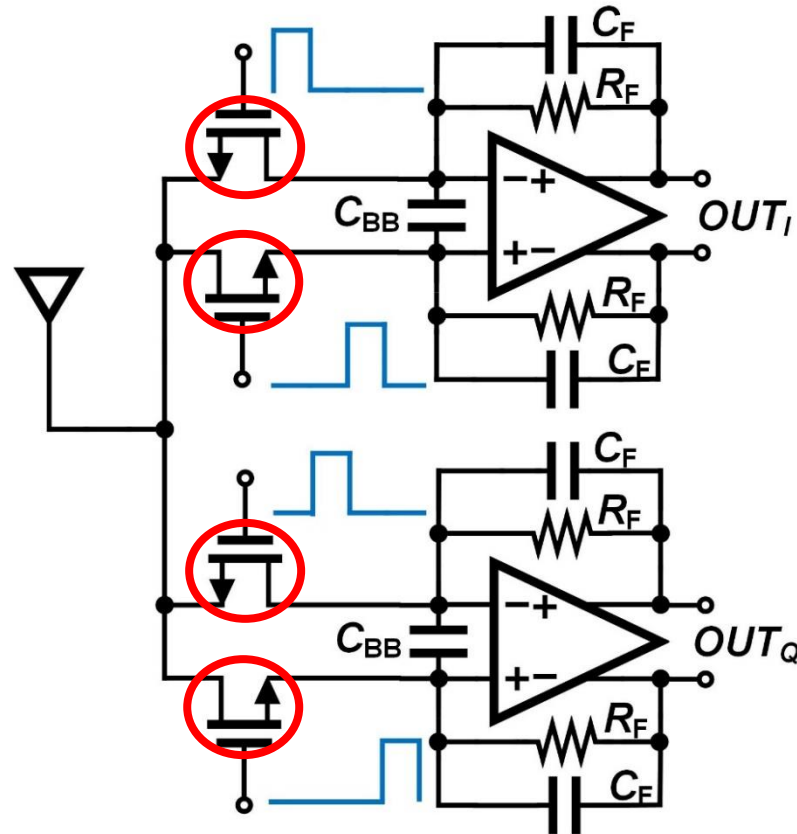


PSP Model Versus SSP Model

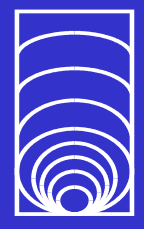
SSP Model	PSP
<ul style="list-style-type: none">✓ Less than 20 parameters× Ignores temperature variation and process corners× Only used for transistors operating as a switch	<ul style="list-style-type: none">× Hundreds of parameters✓ Includes temperature variations and process corners✓ All regions of operation



PSP Model Versus SSP Model

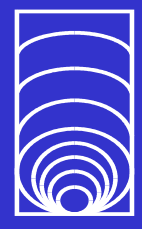


Only transistors operating as a switch are replaced with the SSP model.

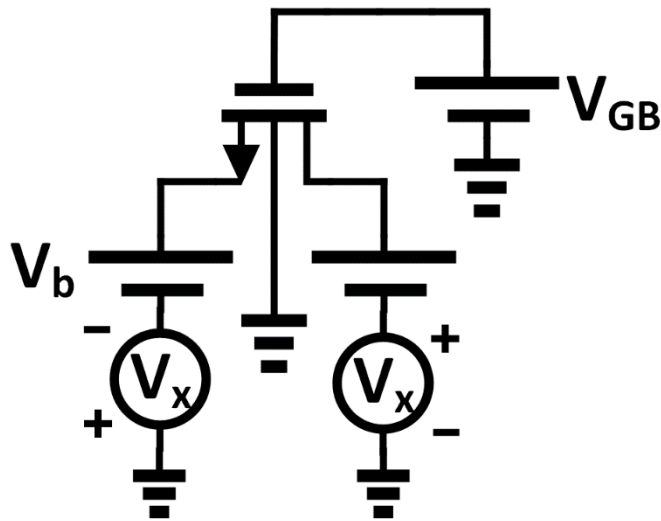


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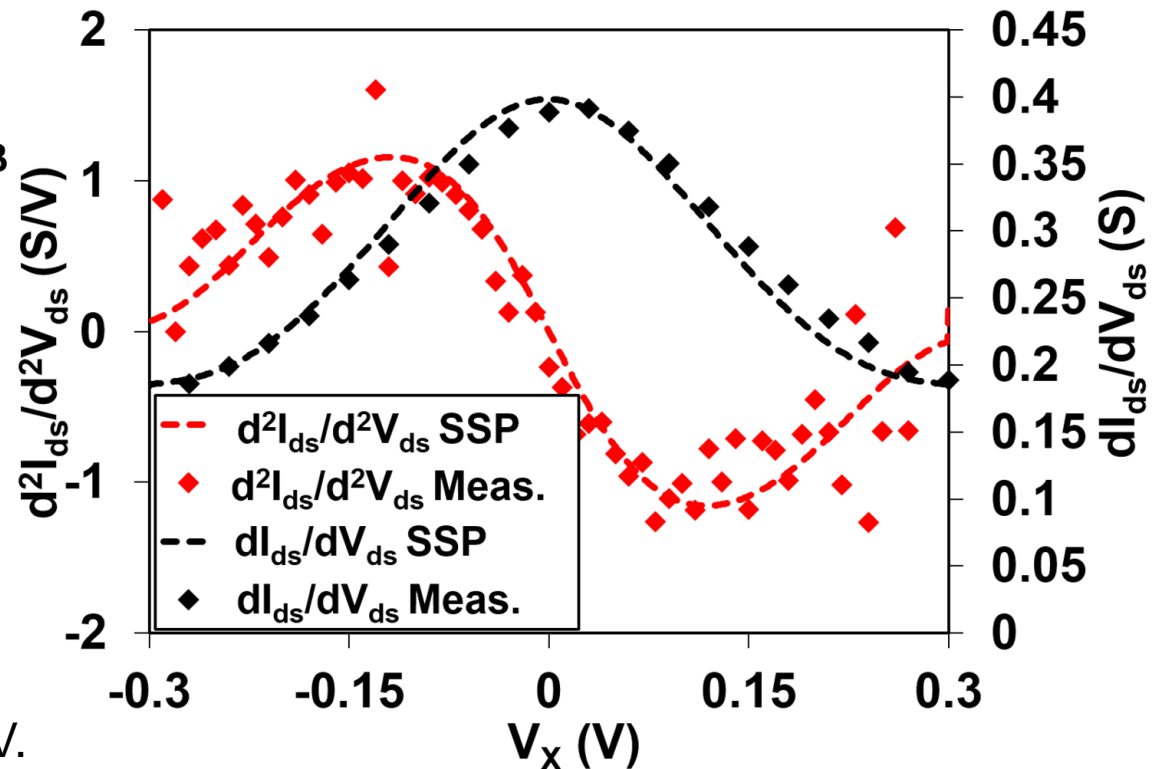
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Measured Gummel Symmetry Test



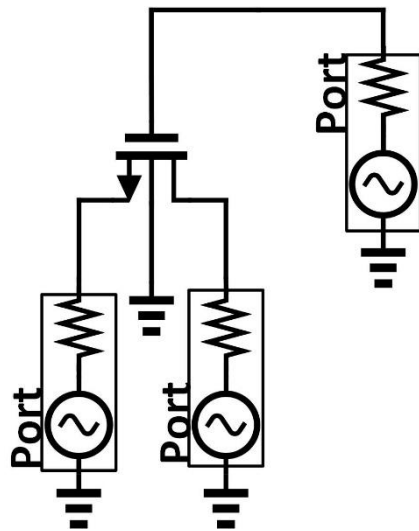
- 65nm CMOS;
- FET size: $\frac{96\mu m}{65nm}$;
- $V_{GB} = 1.2V$ and $V_b = 0.3V$.



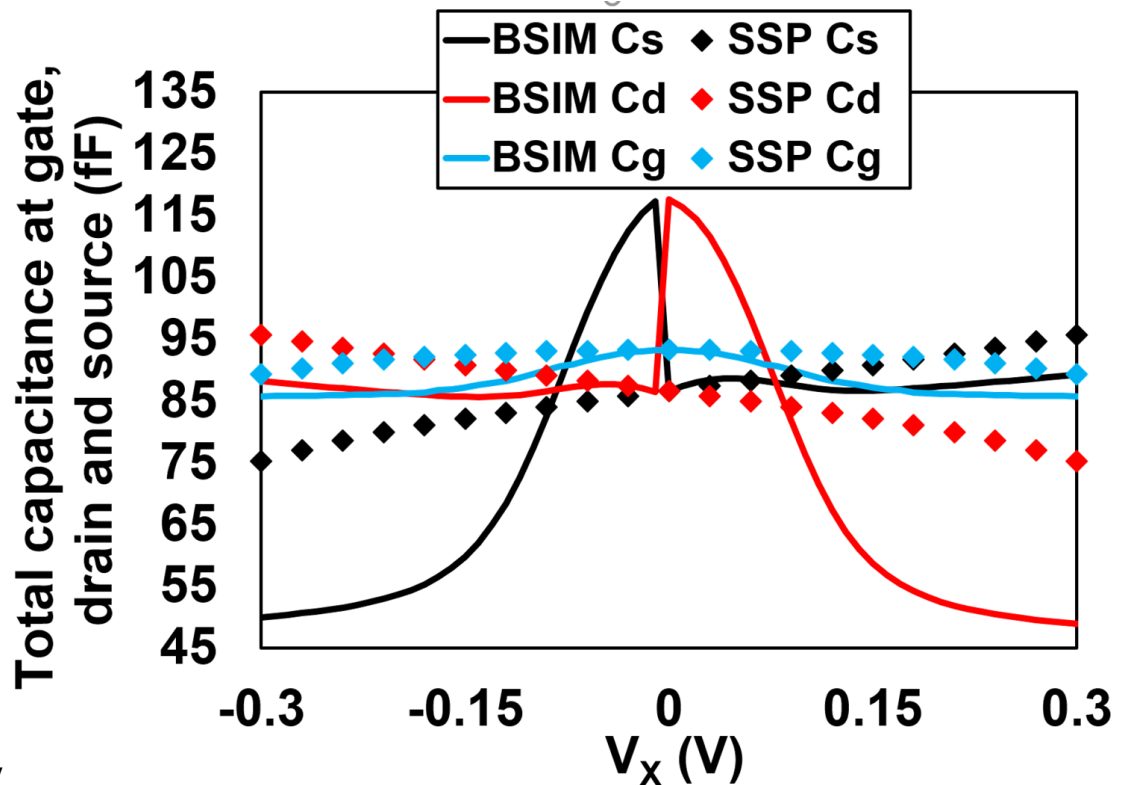
The SSP model accurately predicts I_{DS} and its derivatives.



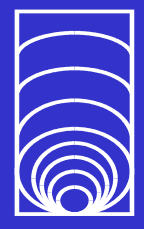
Terminal Capacitance Simulation



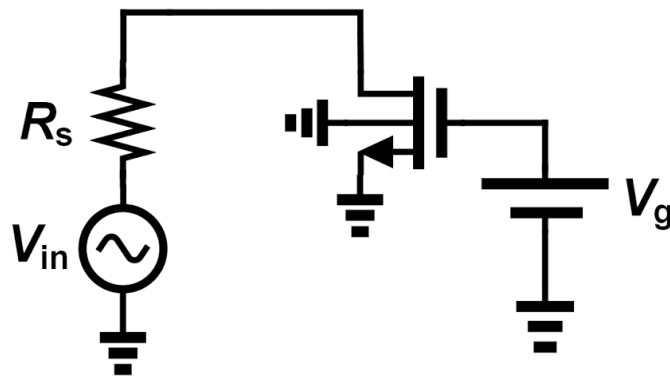
- All capacitors: 1F
- All Inductors: 1H
- 65nm CMOS;
- FET size: $\frac{96\mu m}{65nm}$;
- $V_{GB} = 1.2V$ and $V_b = 0.3V$.



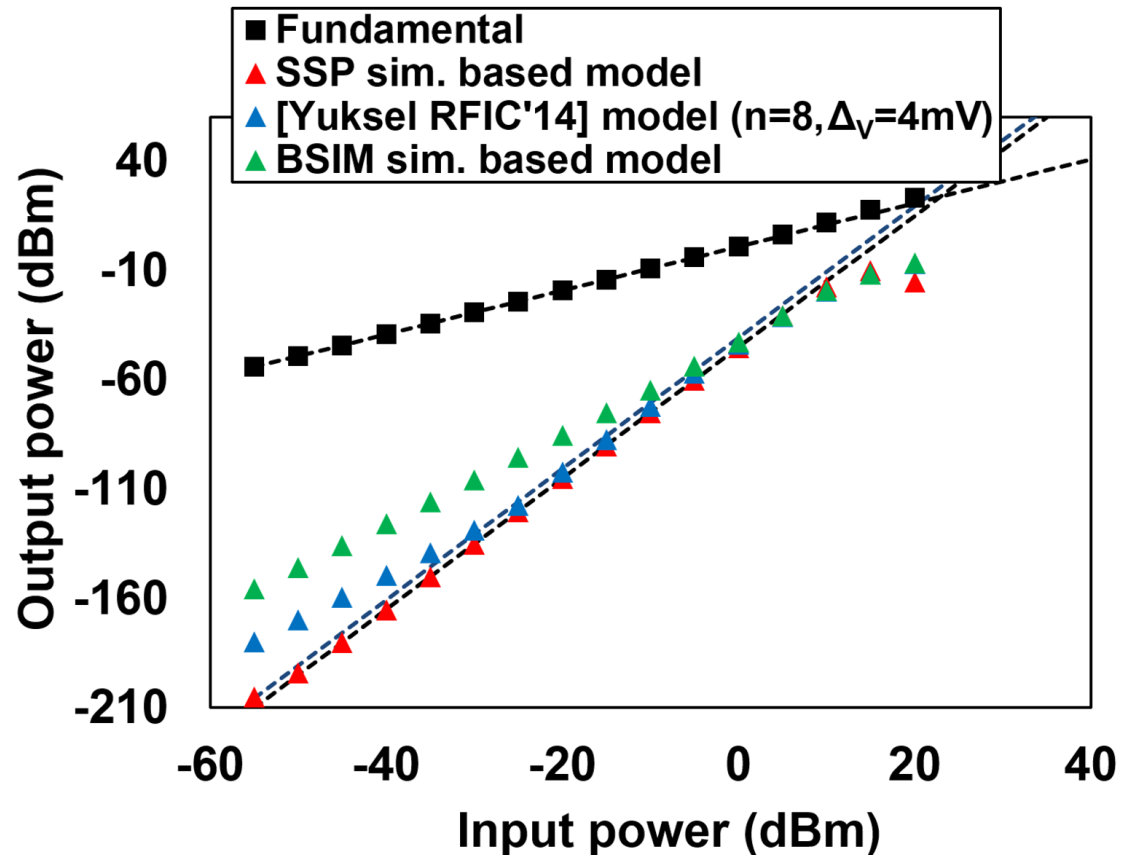
The SSP model fixes the discontinuity in the terminal capacitances.



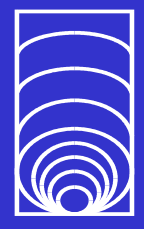
FET IIP_3 Simulation



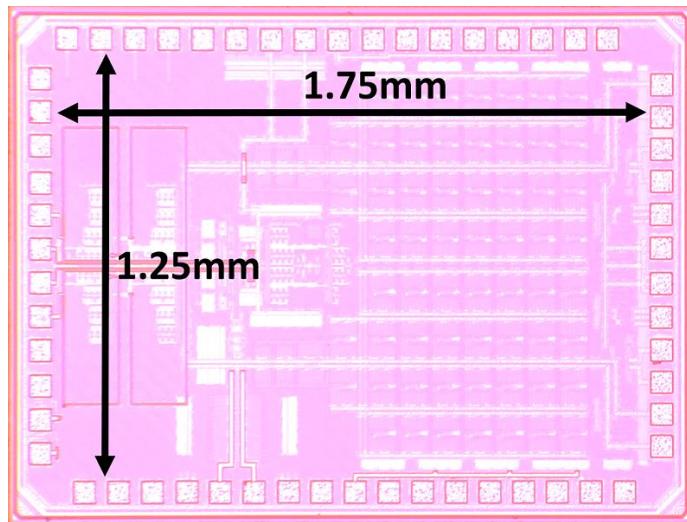
- 65nm CMOS;
- FET size: $\frac{96\mu m}{65nm}$;
- $V_g = 1.2V$.



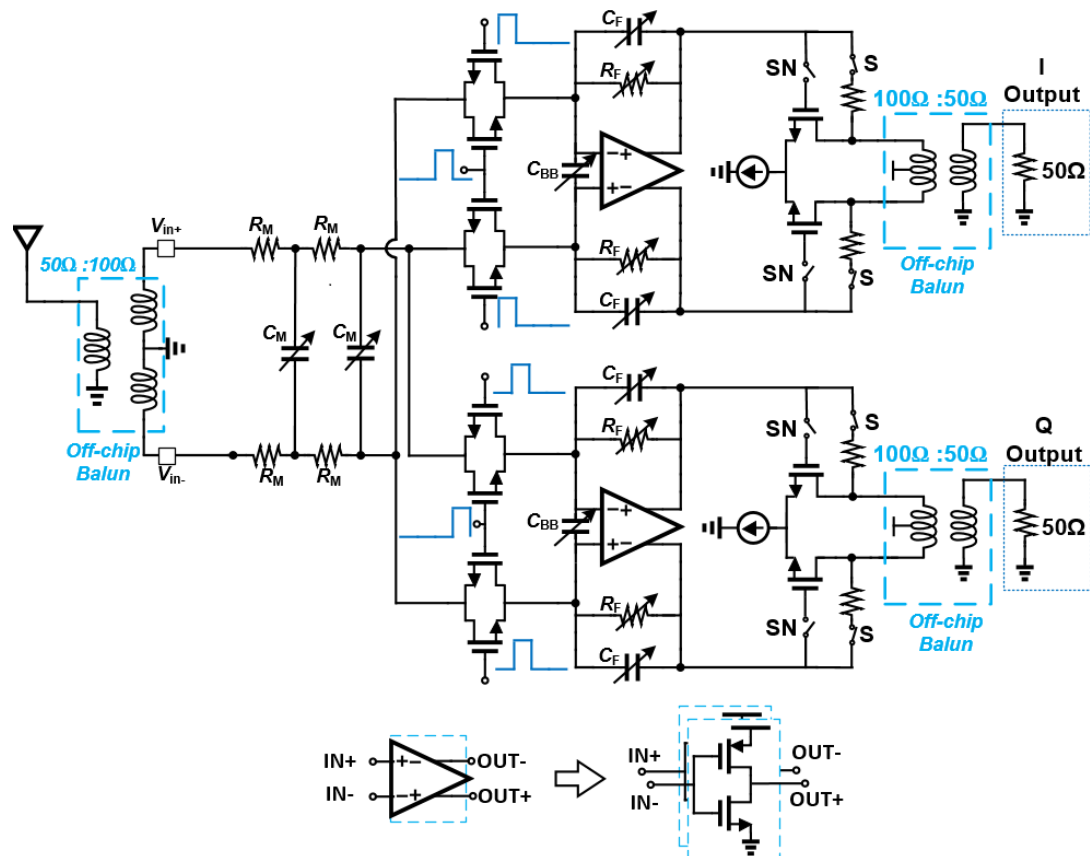
The model predicts 3dB/dB slope for IM_3 for a wide range of drain-source voltage across the FET.

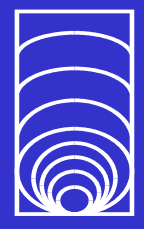


65nm CMOS Mixer-First Receiver

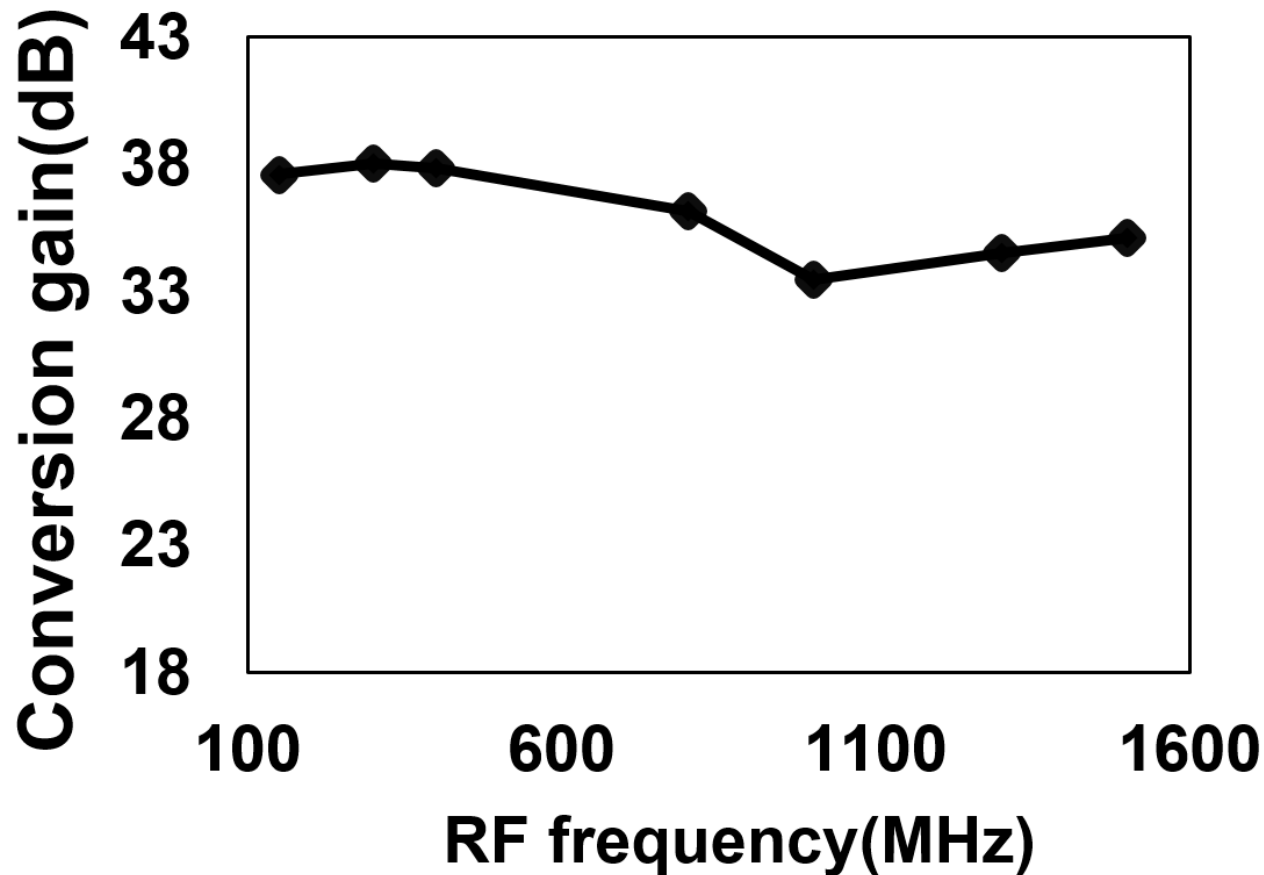


4-Path 0.15-2.5GHz
passive-mixer-first receiver
in 65nm CMOS.



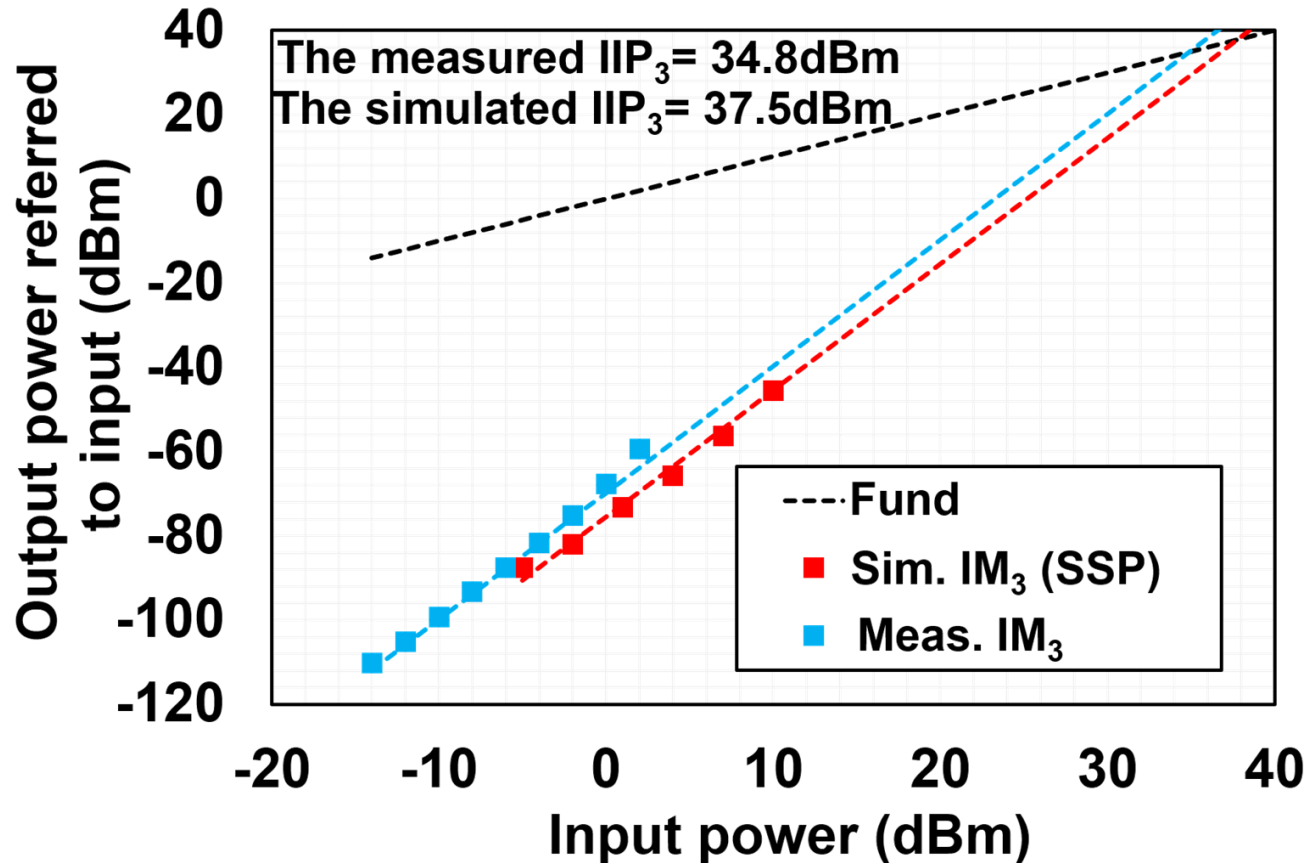


Mixer-First Receiver Gain



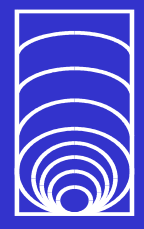


Mixer-First Receiver Out-of-Band IIP_3



The LO frequency is 300MHz and input tones are applied at 500MHz and 699MHz.

The SSP model predicts IIP_3 with better than 3dB precision.



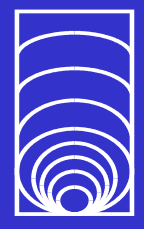
Comparison Table

	This work	[Yuksel 14]
Mixer-first receiver OOB-IIP ₃ simulation accuracy	3dB (4-phase)	4dB* (8-phase)
Single switch simulation time(s)**	0.298	1.2
Mixer first receiver simulation time(min)	56***	Not feasible

*This is an 8-phase mixer-first receiver reported in [Andrews JSSC'10].

**The computer is equipped with quad-core i7 CPU and 32GB physical memory, and simulations are performed on schematic level.

***Simulation is performed with the PSS-shooting method with number of harmonics equal to 175, the LO frequency is 300MHz and tones are applied at 500MHz and 680MHz and simulation is done for 3 power level point.



Outline

- Motivation and Prior Art
- Simplified Surface Potential Model
- Short-Channel Effects
- Simulation and Measurement Results
- Conclusion



Conclusion

- Digitally-driven foundries typically provide BSIM4 models that yield unphysical results when simulating passive mixer-like circuits.
- A simplified surface potential model is introduced that does not require measurements for model fitting, and leverages the foundry-provided models for capturing second-order parasitics.
- The SSP model is more computationally relaxed than prior art, and shows greater accuracy in simulating linearity of passive-mixer-like circuits.
- The model is available at cosmic.ee.columbia.edu for download.